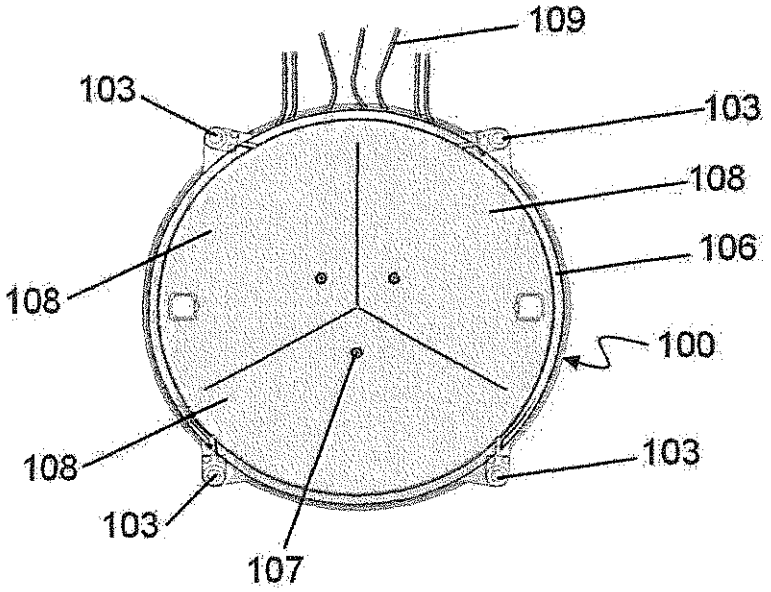

109
103
103
108
106
108
100
108
103
103
107

Fig. 1a

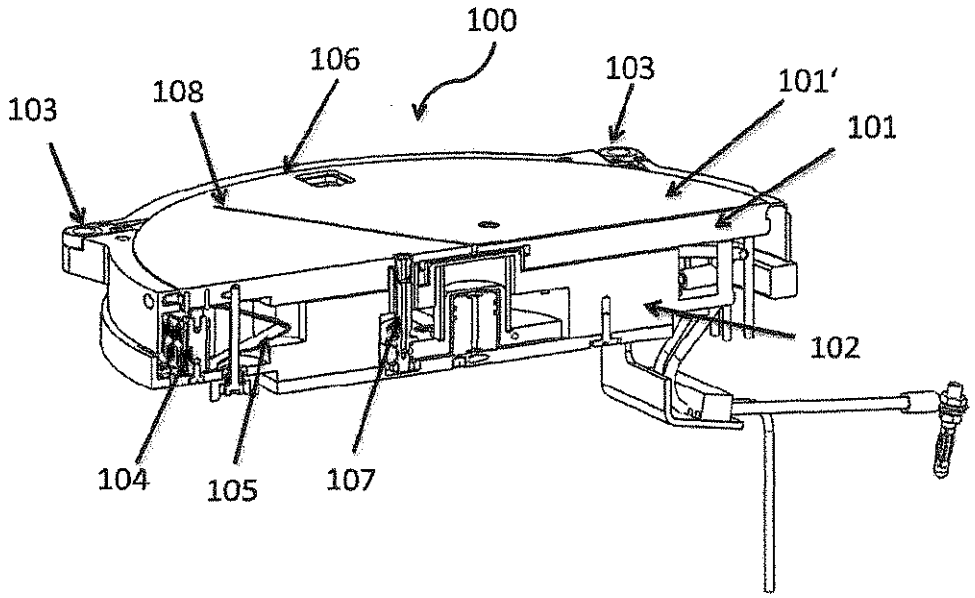

100
106
103
101'
103
108
101
102
104
105
107

Fig. 1b

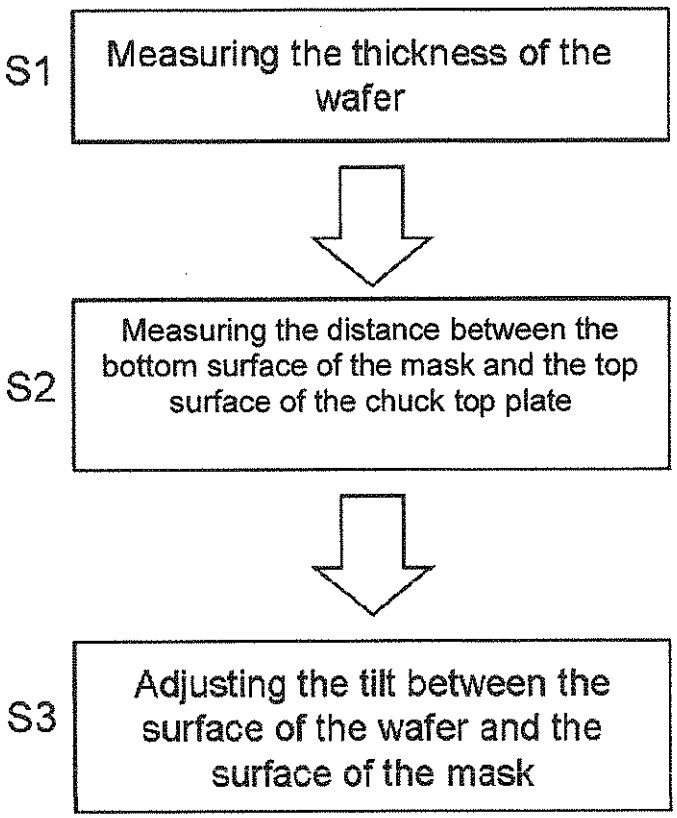

S1
Measuring the thickness of the wafer
S2
Measuring the distance between the bottom surface of the mask and the top surface of the chuck top plate
S3
Adjusting the tilt between the surface of the wafer and the surface of the mask

Fig. 2a

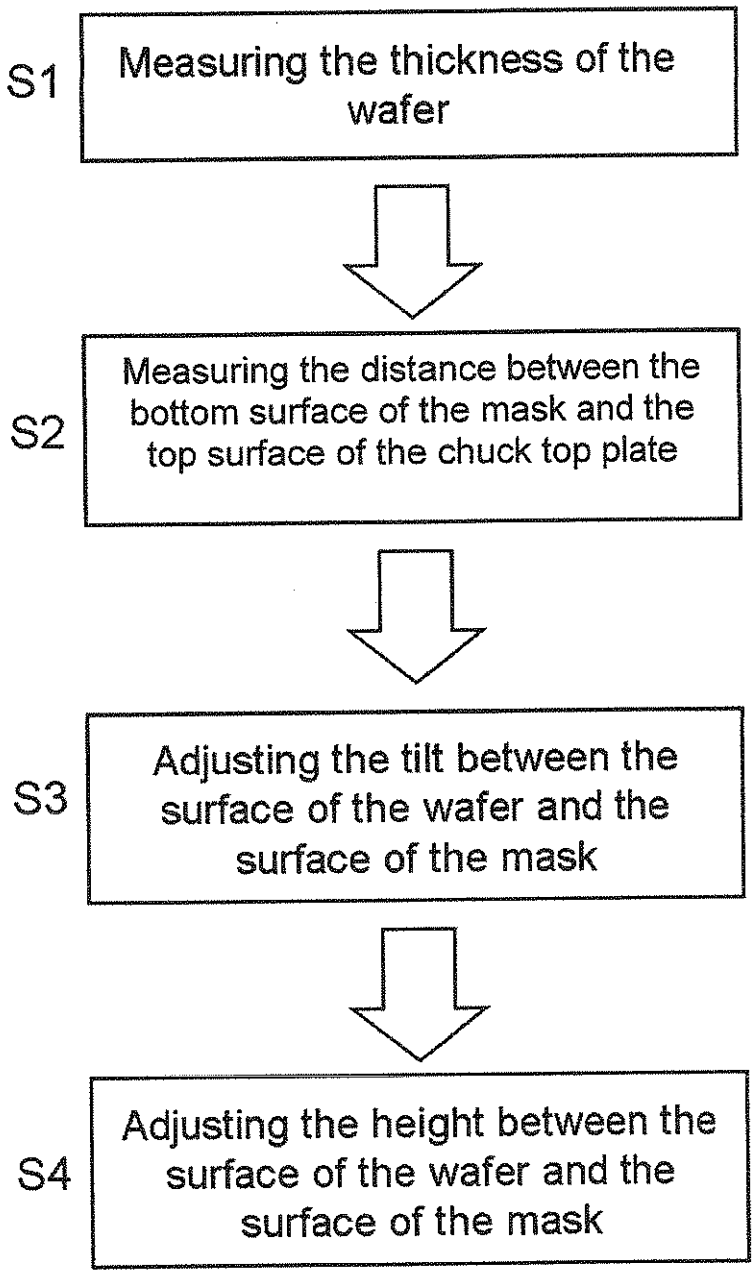

S1
Measuring the thickness of the wafer
S2
Measuring the distance between the bottom surface of the mask and the top surface of the chuck top plate
S3
Adjusting the tilt between the surface of the wafer and the surface of the mask
S4
Adjusting the height between the surface of the wafer and the surface of the mask

Fig. 2b

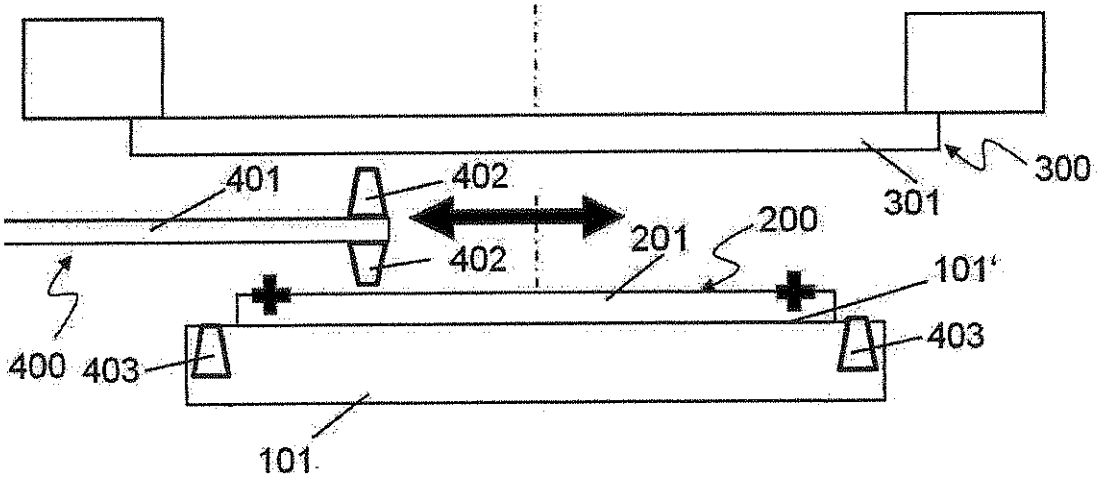

300
301
401
402
402
201
200
101'
400
403
403
101

Fig. 3a

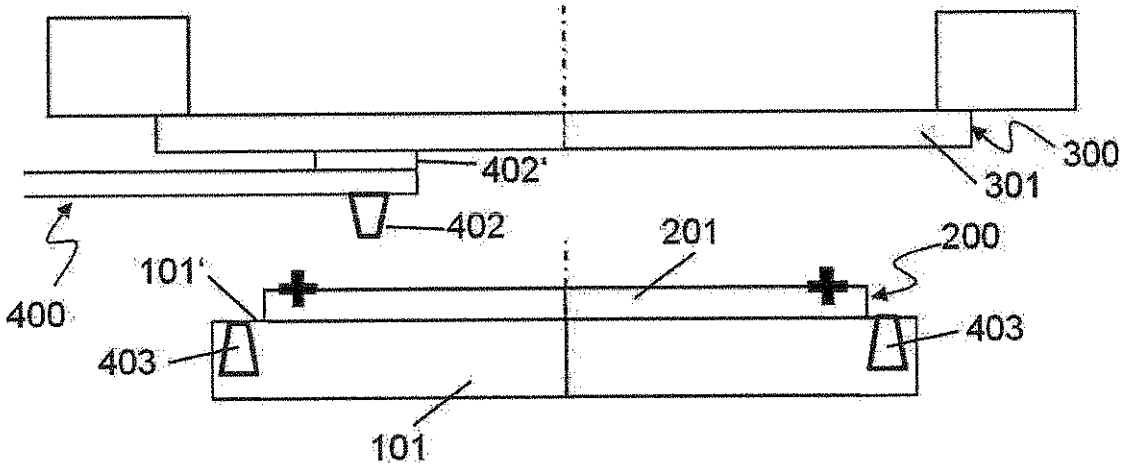

300
301
402'
402
201
200
101'
400
403
403
101

Fig. 3b

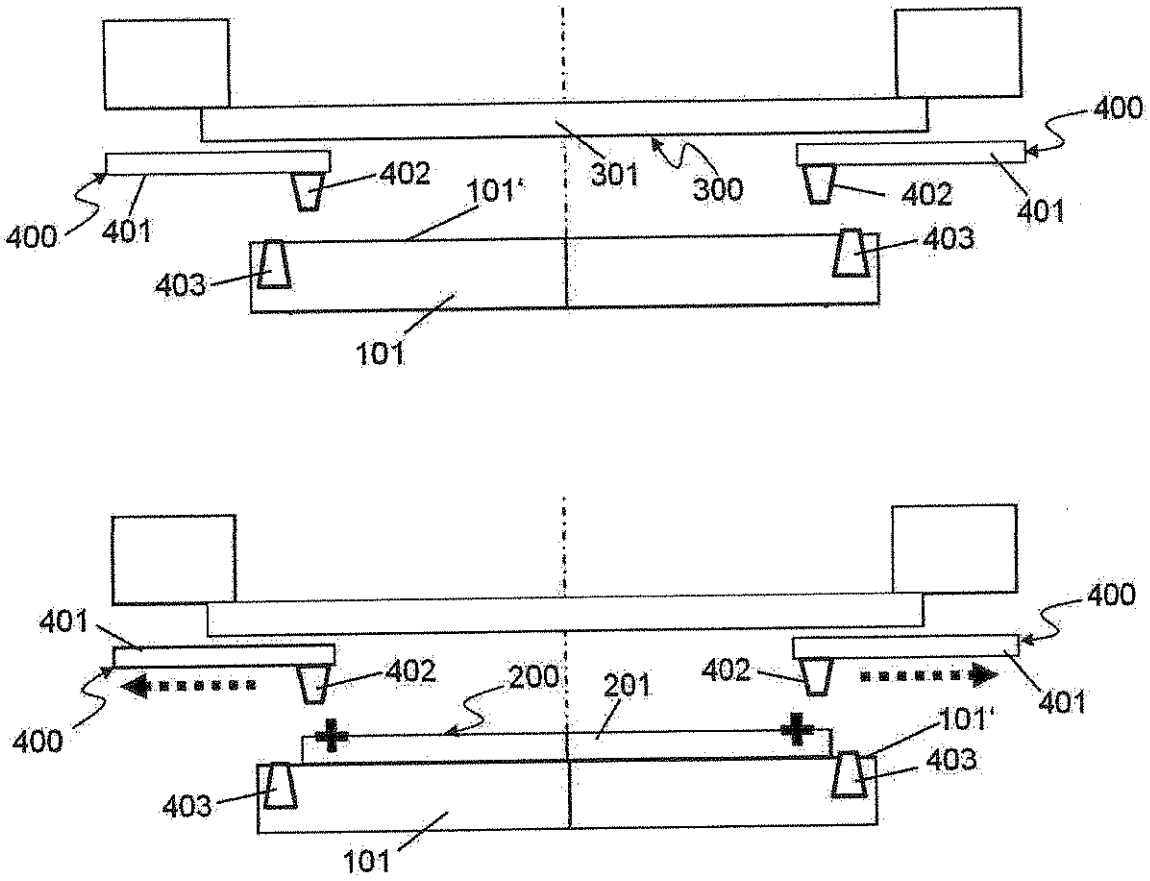

400
402
101'
301
300
402
401
400
401
403
403
101
401
400
402
200
201
402
401
400
101'
403
403
101

Fig. 3c